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CORRECTION

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Correction: Reliable high work-function molybdenum dioxide synthesis *via* template-effect-utilizing atomic layer deposition for next-generation electrode applications

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Correction for 'Reliable high work-function molybdenum dioxide synthesis *via* template-effect-utilizing atomic layer deposition for next-generation electrode applications' by Ye Won Kim *et al.*, *J. Mater. Chem. C*, 2022, **https://doi.org/10.1039/d2tc02104h**.

The authors regret that an incorrect version of Fig. 1(b) appeared in the published article. The corrected version of Fig. 1 and its caption are reproduced here.

The Royal Society of Chemistry apologises for these errors and any consequent inconvenience to authors and readers.

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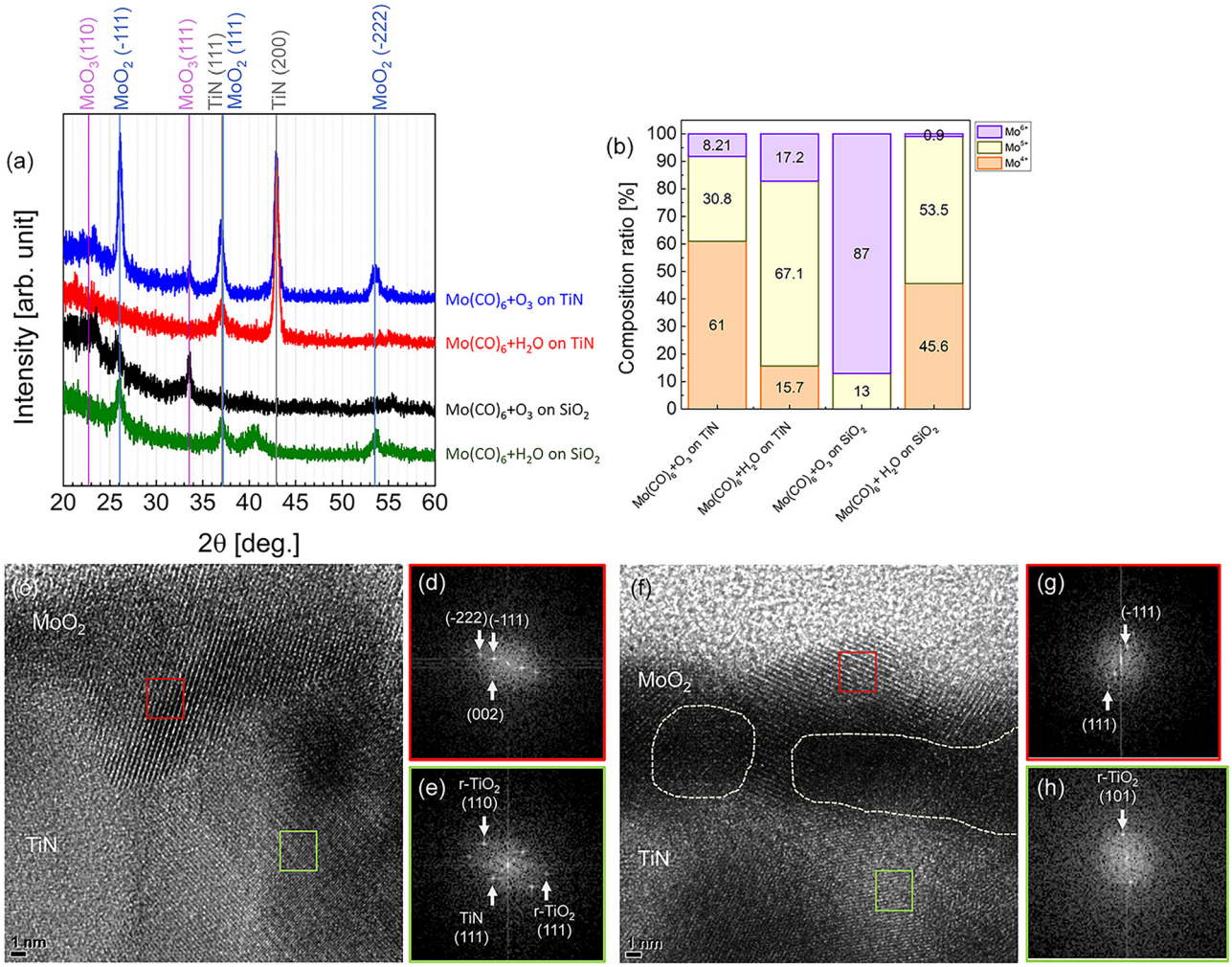

Fig. 1 (a) XRD patterns and (b) composition ratio of oxidation states of MoO_x thin films deposited under various conditions. (c) HR-TEM image of TiN/MoO_x deposited using O_3 and FFT patterns of (d) MoO_2 (indicated by red box in (c)) and (e) TiN surface (indicated by green box in (c)). (−111), (111), and (−222) in (d) indicate the planes of monoclinic phase MoO_2. r-TiO_2 in (e) indicates rutile-phased TiO_2. (f) HR-TEM image of TiN/MoO_x deposited using H_2O. The dashed line region indicates an amorphous area in the film. FFT patterns of (g) MoO_2 (indicated by red box in (f)) and (h) the TiN surface (indicated by the green box in (f)).